

*Fig. 1*

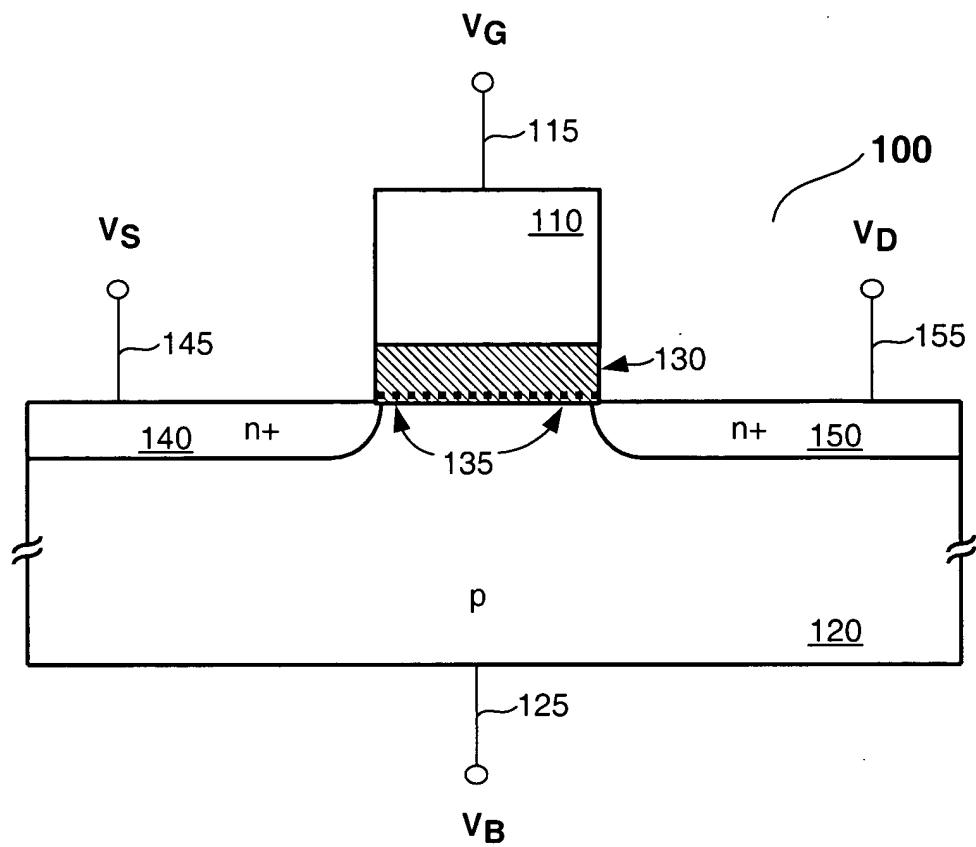
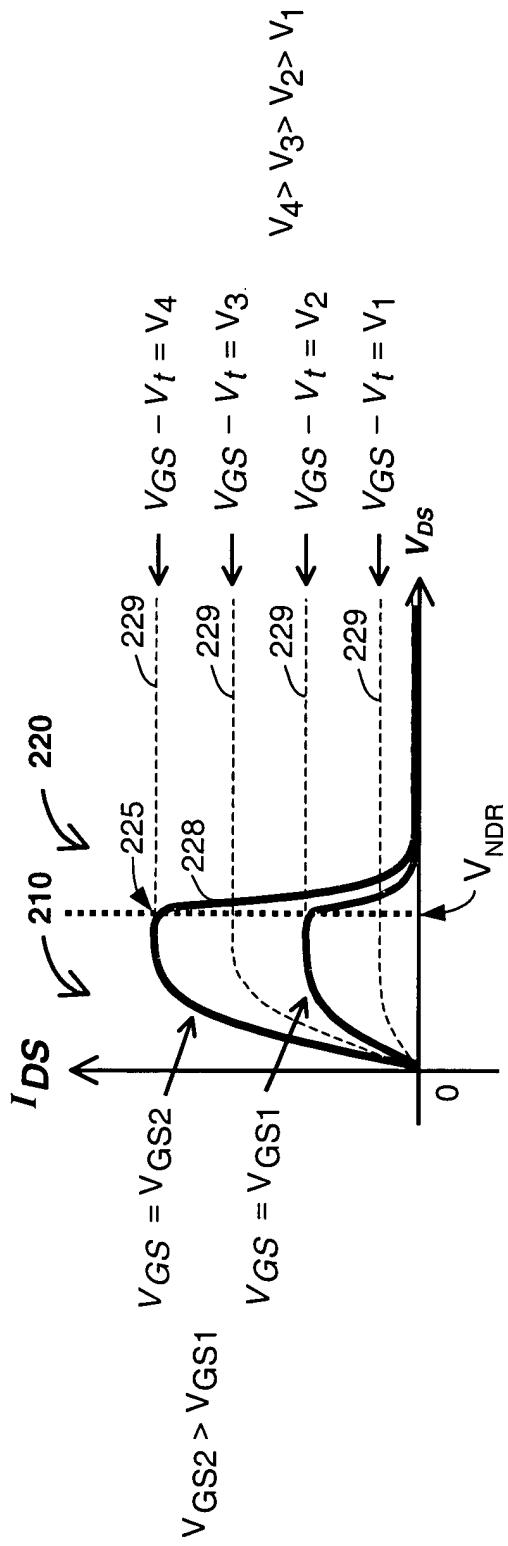
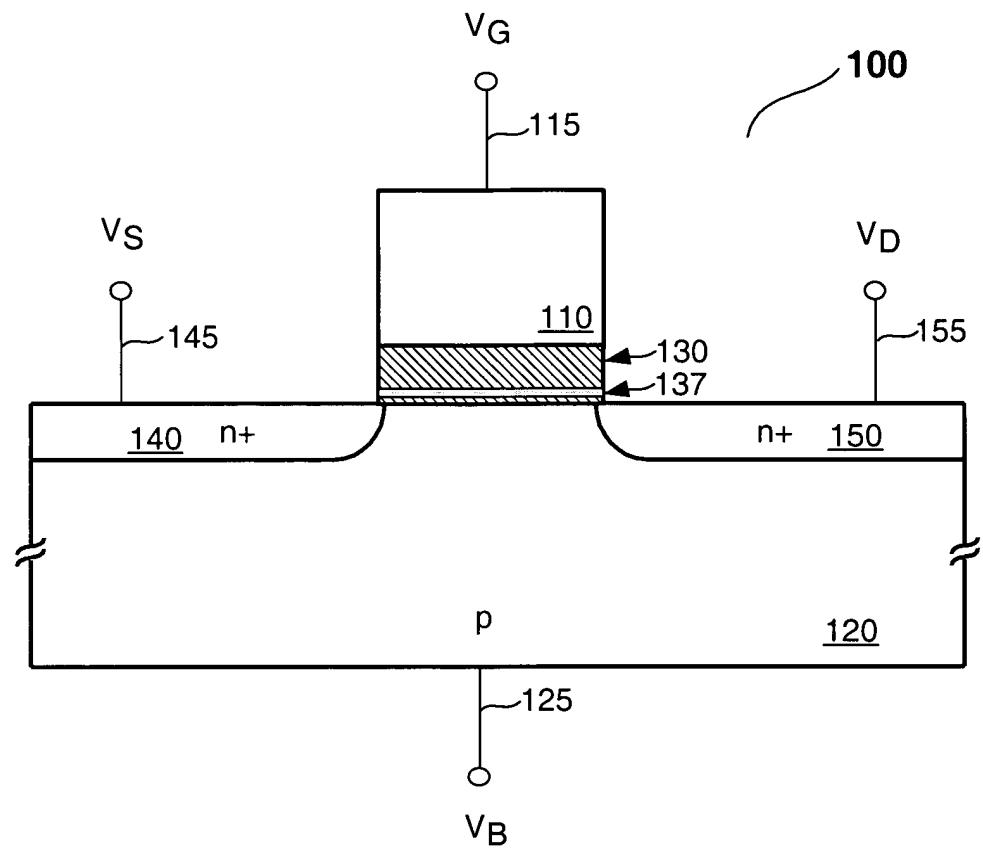


Fig. 2



*Fig. 3*



*Fig. 4*

Standard CMOS Starting Material
Standard CMOS Isolation Process
NDR Surface Doping Process Sequence
NDR Device Gate Insulator Formation
N-well Dopant Process Sequence (for PMOS)
P-well Dopant Process Sequence (For NMOS)
Logic Device Gate Oxidation
Gate Material Deposition and Patterning
NDR Drain Junction Engineering Sequence
Source/Drain Pattern and Process Sequence
Oxide Deposition
Contact Process Sequence
Metal Process Sequence

Fig. 5

